

Att. Docket No. 10191/1629

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. Serial No. : 09/720,761 Confirmation No. 5642

Title : METHOD OF PLASMA
ETCHING OF SILICON

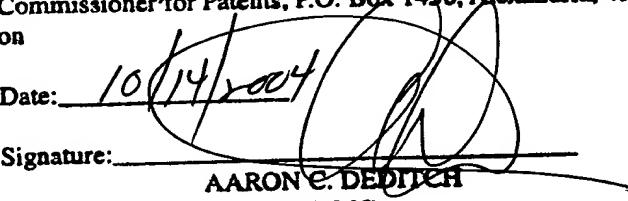
Applicant(s) : Franz LAERMER et al.

Filed : March 26, 2001

TC/A.U. : 1765

Examiner : Kin Chan Chen

Docket No. : 10191/1629 I hereby certify that this correspondence is being deposited with the
United States Postal Service with sufficient postage as first class mail
in an envelope addressed to:

Customer No. : 26646 Mail Stop AF
Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450
on
Date: 10/14/2004
Signature: 

AARON C. DEDITCH
(33,865)

TRANSMITTAL

SIR:

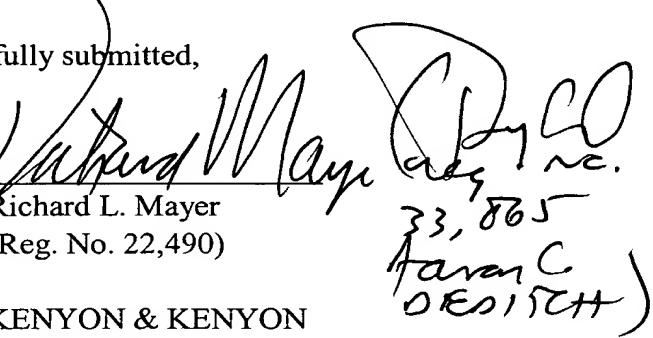
Transmitted herewith for filing in the above-identified patent application is an Amendment
After A Final Office Action.

This is also a Petition under 37 C.F.R. § 1.136(a) to extend the three-months response date
by two months from September 7, 2004 to November 7, 2004.

The Commissioner is authorized to charge the appropriate fees, which are believed to be
\$430.00 for the two-months extension, to Deposit Account No. **11-0600**, and is also authorized, as
appropriate and/or necessary, to charge any additional fees (including any Rule 136(a) extension
fees) or credit any overpayment to Deposit Account No. **11-0600**. Two duplicate copies of this
transmittal letter are enclosed for that purpose

Respectfully submitted,

Dated: 10/14/2004

By: 

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